



Ordering in thin films of block copolymers: Fundamentals to potential applications

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ABSTRACT

The ordering of block copolymers in thin films is reviewed, starting from the fundamental principles and extending to recent promising developments as templates for nanolithography which may find important applications in the semiconductor industry. Ordering in supported thin films of symmetric and asymmetric AB diblock and ABA triblock copolymers is discussed, along with that of more complex materials such as ABC triblocks and liquid crystalline block copolymers. Techniques to prepare thin films, and to characterise ordering within them, are summarized. Several methods to align block copolymer nanostructures, important in several applications are outlined. A number of potential applications in nanolithography, production of porous materials, templating, and patterning of organic and inorganic materials are then presented. The influence of crystallization on the morphology of a block copolymer film is briefly discussed, as are structures in grafted block copolymer films.

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Contents

1. Introduction.....	1162
2. Preparation of block copolymer films.....	1163
2.1. Spin- and dip-coating.....	1163
2.2. Dewetting.....	1163
2.3. Solvent annealing.....	1164
3. Techniques to investigate ordering in block copolymer films.....	1165
3.1. AFM.....	1165
3.2. SEM.....	1166

Abbreviations: AFM, atomic force microscopy; GISANS, grazing-incidence small-angle neutron scattering; GISAXS, grazing-incidence small-angle X-ray scattering; HDMS, hexamethyldisilazane; hPB, hydrogenated polybutadiene; HSQ, hydrogen silsesquioxane; L_0 , (bulk) domain spacing of block copolymer structure; LC, liquid crystal(line); P α MS, poly(α -methyl styrene); PAH, poly(allylamine hydrochloride); PAN, polyacrylonitrile; PaPV, poly(alkoxyphenylenevinylene); PtBA, poly(*tert*-butyl acrylate); PBMA, poly(butyl methacrylate); PnBMA, poly(*n*-butyl methacrylate); PtBMA, poly(*tert*-butyl methacrylate); PBO, (polybutylene oxide)-poly(oxybutylene); PCHE, poly(cyclohexylethylene); PCHEMA, poly(2-(3-cholesteryl-oxycarbonyloxy)ethylmethacrylate); PDXO, poly(1,5-dioxepan-2-one); PE, polyethylene; PEE, poly(ethyl ethylene); PEO, poly(ethylene oxide)=poly(oxyethylene); PEP, poly(ethylene propylene); PFEMS, poly(ferrocenyl ethylmethylsilane); PFS, poly(ferrocenyl dimethylsilane); PGMA, poly(glycidyl methacrylate); PHEMA, poly(hydroxyethyl methacrylate); PI, poly(isoprene); PIOH, hydroxylated poly(isoprene); PIBVE, poly(isobutyl vinyl ether); PLLA, poly(L-lactide); PMAA, poly(methacrylic acid); PMMA, poly(methyl methacrylate); PMB, poly(3-methyl-1-butene); PMS, poly(methylstyrene); PpMS, poly(*p*-methylstyrene); PS, polystyrene; PSEB, poly(styrene-*ran*-ethylene-*ran*-butene); P2VP, poly(2-vinylpyridine); RIE, reactive ion etching; SAM, self-assembled monolayer; SAXS, small-angle X-ray scattering; SCF(T), self-consistent field (theory); SEBS, polystyrene-poly(ethylene-co-butylene)-polystyrene; SEM, scanning electron microscopy; SIMS, secondary ion mass spectroscopy; *t*, film thickness; TEM, transmission electron microscopy; TOF-SIMS, time-of-flight secondary ion mass spectroscopy.

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3.3.	X-ray and neutron reflectivity and grazing incidence small-angle X-ray scattering (GISAXS) or grazing incidence small-angle neutron scattering (GISANS).....	1166
3.4.	Secondary ion mass spectrometry	1167
3.5.	Optical microscopy	1167
3.6.	Ellipsometry	1167
3.7.	Others	1167
4.	Block copolymer microphase separation in thin films—symmetric diblocks	1167
4.1.	Interface thickness	1167
4.2.	Film thickness quantization and island-and-hole formation	1167
4.3.	Surface-induced ordering	1168
4.4.	Films constrained at both surfaces	1170
4.5.	Surface segregation	1170
4.6.	Ultrathin (monolayer) films	1171
5.	Block copolymer microphase separation in thin films—asymmetric diblocks	1171
5.1.	Cylinder-forming diblocks	1171
5.2.	Sphere-forming diblocks	1172
5.3.	Swelling with homopolymers	1173
5.4.	Morphology transitions in asymmetric diblocks	1174
6.	Microdomain orientation	1175
6.1.	Neutral brushes for perpendicular alignment	1175
6.2.	Chemical patterning	1177
6.3.	Electric field alignment	1179
6.4.	Graphoepitaxy	1181
6.4.1.	Lamellae	1181
6.4.2.	Cylinders	1182
6.4.3.	Spheres	1182
6.5.	Contact line pinning	1184
6.6.	Soft lithography	1184
6.7.	Shear alignment	1184
6.8.	Directional crystallization	1184
6.9.	Zone annealing	1184
7.	Block copolymer nanolithography	1184
8.	Nanoporous structures	1187
8.1.	Patterning of inorganic (especially magnetic) materials in nanoporous films	1187
8.2.	Membranes	1190
9.	Block copolymer films as templates	1192
9.1.	Templates for inorganic material patterning	1192
9.2.	Templates for biomolecule patterning	1195
10.	Miscellaneous applications	1196
11.	Block copolymer microphase separation in thin films—ABC triblocks	1196
12.	Liquid crystal block copolymers	1198
13.	Crystalline block copolymers	1199
14.	Grafted block copolymer films	1202
15.	Blends of block copolymers	1202
16.	Conclusions	1203
	References	1203

1. Introduction

This review is focussed on the ordering of block copolymers in thin films, prepared by spin coating or dip coating methods. In such films, self-assembly of lamellar, cylindrical or spherical domain structures has been extensively investigated for diblock copolymers. These phases also exist in the bulk melt of diblock copolymers [1], although surfaces have a profound effect on ordering, as highlighted herein. The bicontinuous cubic gyroid structure also found in the diblock phase diagram cannot exist in two dimensions. In films of ABC triblocks, other distinct morphologies can exist in two dimensions and what studies there are to date on this are also reviewed.

Potential applications of block copolymer films are now emerging in areas such as high density data storage,

nanolithography and others and approaches to achieving technologically useful processing methods with such objectives are discussed in detail.

Ordering in block copolymer thin films has been the subject of a number of previous dedicated reviews [2–6], as well as discussion in a text on block copolymers [1]. Several reviews among these, and others, are focussed on nanopatterning applications [3–5,7–14]. A review on thin films of complexed block copolymers (a topic not considered here) is also available [15]. This is focussed on supramolecular block copolymer (e.g. hydrogen bonded) systems as well as complexes with nanoparticles. A number of reviews have touched on aspects of the theory of ordering in block copolymer films [16,17]. This review covers both experimental and theoretical aspects.

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